Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
LÍ.	1	FinFET and hydrogen near5 (implanted or dopant) near5 (semiconductor or silicon)	USPAT; EPO; JPO; DERWENT	OR	OFF	2004/12/05 18:14
L2	46	MOSFET and hydrogen near5 (implanted or dopant) near5 (semiconductor or silicon)	USPAT; EPO; JPO; DERWENT	OR	OFF	2004/12/05 18:15